

Polymers for Microelectronics

Resists and Dielectrics

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Contents

Preface	xi
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CHEMICALLY AMPLIFIED RESISTS

1. Chemical Amplification Mechanisms for Microlithography.....	2
E. Reichmanis, F. M. Houlihan, O. Nalamasu, and T. X. Neenan	
2. Synthesis of 4-(<i>tert</i>-Butoxycarbonyl)-2,6-dinitrobenzyl Tosylate: A Potential Generator and Dissolution Inhibitor Solubilizable through Chemical Amplification	25
F. M. Houlihan, E. Chin, O. Nalamasu, and J. M. Kometani	
3. Chemically Amplified Deep-UV Photoresists Based on Acetal-Protected Poly(vinylphenols)	40
Ying Jiang and David R. Bassett	
4. Novel Analytic Method of Photoinduced Acid Generation and Evidence of Photosensitization via Matrix Resin	53
N. Takeyama, Y. Ueda, T. Kusumoto, H. Ueki, and M. Hanabata	
5. Acid-Catalyzed Dehydration: A New Mechanism for Chemically Amplified Lithographic Imaging.....	64
H. Ito, Y. Maekawa, R. Sooriyakumaran, and E. A. Mash	
6. An Alkaline-Developable Positive Resist Based on Silylated Polyhydroxystyrene for KrF Excimer Laser Lithography	88
Eiichi Kobayashi, Makoto Murata, Mikio Yamachika, Yasutaka Kobayashi, Yoshiji Yumoto, and Takao Miura	
7. A Test for Correlation between Residual Solvent and Rates of <i>N</i>-Methylpyrrolidone Absorption by Polymer Films.....	101
W. D. Hinsberg, S. A. MacDonald, C. D. Snyder, H. Ito, and R. D. Allen	

8. **Dissolution Rates of Copolymers Based on 4-Hydroxystyrene and Styrene** 111
C.-P. Lei, T. Long, S. K. Obendorf, and F. Rodriguez
9. **Synthesis and Polymerizations of *N*-(*tert*-Butoxy)maleimide and Application of Its Polymers as a Chemical Amplification Resist**..... 124
Kwang-Duk Ahn and Deok-Il Koo
10. **Acid-Sensitive Pyrimidine Polymers for Chemical Amplification Resists** 142
Yoshiaki Inaki, Nobuo Matsumura, and Kiichi Takemoto
11. **Methacrylate Terpolymer Approach in the Design of a Family of Chemically Amplified Positive Resists** 165
R. D. Allen, G. M. Wallraff, W. D. Hinsberg,
L. L. Simpson, and R. R. Kunz

TOP-SURFACE IMAGING AND
DRY DEVELOPMENT RESISTS

12. **Surface-Imaging Resists Using Photogenerated Acid-Catalyzed SiO₂ Formation by Chemical Vapor Deposition**..... 180
Masamitsu Shirai and Masahiro Tsunooka
13. **Polysilphenylenesiloxane Resist with Three-Dimensional Structure**..... 194
K. Watanabe, E. Yano, T. Namiki, and Y. Yoneda
14. **Top-Surface Imaging Using Selective Electroless Metallization of Patterned Monolayer Films**..... 210
J. M. Calvert, W. J. Dressick, C. S. Dulcey, M. S. Chen,
J. H. Georger, D. A. Stenger, T. S. Koloski, and
G. S. Calabrese
15. **Langmuir-Blodgett Deposition To Evaluate Dissolution Behavior of Multicomponent Resists** 220
V. Rao, W. D. Hinsberg, C. W. Frank, and R. F. W. Pease
16. **Photochemical Control of a Morphology and Solubility Transformation in Poly(vinyl alcohol) Films Induced by Interfacial Contact with Siloxanes and Phenol-Formaldehyde Polymeric Photoresists** 235
James R. Sheats

ELECTRON-BEAM, X-RAY, AND PHOTORESISTS

17. **Advances in the Chemistry of Resists for Ionizing Radiation**..... 252
 Ralph Dammel
18. **Out-of-Plane Expansion Measurements in Polyimide Films**..... 282
 Michael T. Pottiger and John C. Coburn
19. **Radiation-Induced Modifications of Allylamino-Substituted Polyphosphazenes** 293
 M. F. Welker, H. R. Allcock, G. L. Grune, R. T. Chern, and V. T. Stannett
20. **Synthesis of Perfluorinated Polyimides for Optical Applications** 304
 Shinji Ando, Tohru Matsuura, and Shigekuni Sasaki
21. **Charged Species in σ -Conjugated Polysilanes as Studied by Absorption Spectroscopy with Low-Temperature Matrices** 323
 K. Ushida, A. Kira, S. Tagawa, Y. Yoshida, and H. Shibata
22. **Acid-Sensitive Phenol-Formaldehyde Polymeric Resists**..... 333
 W. Brunsvold, W. Conley, W. Montgomery, and W. Moreau
23. **Superiority of Bis(perfluorophenyl) Azides over Nonfluorinated Analogues as Cross-Linkers in Polystyrene-Based Deep-UV Resists** 348
 Sui Xiong Cai, M. N. Wybourne, and John F. W. Keana
24. **New Photoresponsive Polymers Bearing Norbornadiene Moiety: Synthesis by Selective Cationic Polymerization of 2-(3-Phenyl-2,5-norbornadiene-2-carbonyloxy)ethyl Vinyl Ether and Photochemical Reaction of the Resulting Polymers...** 356
 T. Nishikubo, A. Kameyama, K. Kishi, and C. Hijikata
25. **Photoinitiated Thermolysis of Poly(5-norbornene 2,3-dicarboxylates): A Way to Polyconjugated Systems and Photoresists**..... 370
 Ernst Zenkl, Michael Schimetta, and Franz Stelzer

POLYIMIDES AND DIELECTRIC POLYMERS

26. Recent Progress of the Application of Polyimides to Microelectronics	380
Daisuke Makino	
27. Base-Catalyzed Cyclization of <i>ortho</i>-Aromatic Amide Alkyl Esters: A Novel Approach to Chemical Imidization	403
W. Volksen, T. Pascal, J. W. Labadie, and M. I. Sanchez	
28. Base-Catalyzed Photosensitive Polyimide	417
D. R. McKean, G. M. Wallraff, W. Volksen, N. P. Hacker, M. I. Sanchez, and J. W. Labadie	
29. Novel Cross-Linking Reagents Based on 3,3-Dimethyl-1-phenylenetriazene	428
Aldrich N. K. Lau and Lanchi P. Vo	
30. Preparation of Novel Photosensitive Polyimide Systems via Long-Lived Active Intermediates	440
Takahi Yamashita and Kazuyuki Horie	
31. Photoregulation of Liquid-Crystalline Orientation by Anisotropic Photochromism of Surface Azobenzenes	453
Yuji Kawanishi, Takashi Tamaki, and Kunihiro Ichimura	
32. Factors Affecting the Stability of Polypyrrole Films at Higher Temperatures	466
V.-T. Truong and B. C. Ennis	
33. Intrinsic and Thermal Stress in Polyimide Thin Films	482
M. Ree and D. P. Kirby	
34. Fluorinated, Soluble Polyimides with High Glass-Transition Temperatures Based on a New, Rigid, Pentacyclic Dianhydride: 12,14-Diphenyl-12,14-bis(trifluoromethyl)-12<i>H</i>,14<i>H</i>-5,7-dioxapentacene-2,3,9,10-tetracarboxylic Dianhydride	494
Brian C. Auman and Swiatoslaw Trofimenko	
35. Processable Fluorinated Acrylic Resins with Low Dielectric Constants	507
Henry S.-W. Hu and James R. Griffith	

36. Enhanced Processing of Poly(tetrafluoroethylene) for Microelectronics Applications	517
Charles R. Davis and Frank D. Egitto	
37. Synthesis and Characterization of New Poly(arylene ether oxadiazoles)	526
Frank W. Mercer, Chris Coffin, and David W. Duff	
38. Microstructural Characterization of Thin Polyimide Films by Positron Lifetime Spectroscopy	535
A. Eftekhari, A. K. St. Clair, D. M. Stoakley, Danny R. Sprinkle, and J. J. Singh	
39. Fluorinated Poly(arylene ethers) with Low Dielectric Constants	546
Frank W. Mercer, David W. Duff, Timothy D. Goodman, and Janusz B. Wojtowicz	

INDEXES

Author Index	556
Affiliation Index	557
Subject Index	558